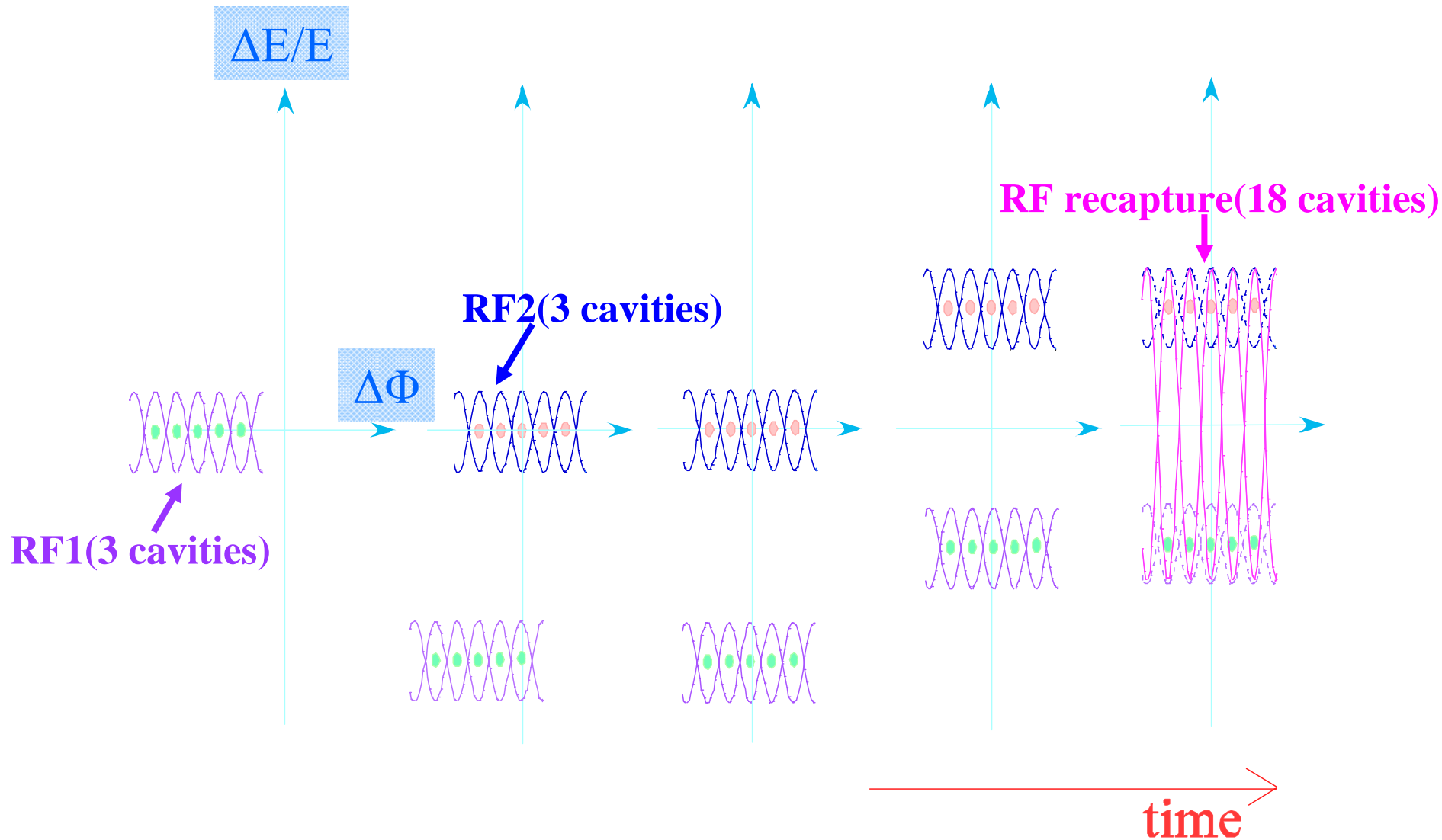


# Slip Stacking Losses-Present and Future

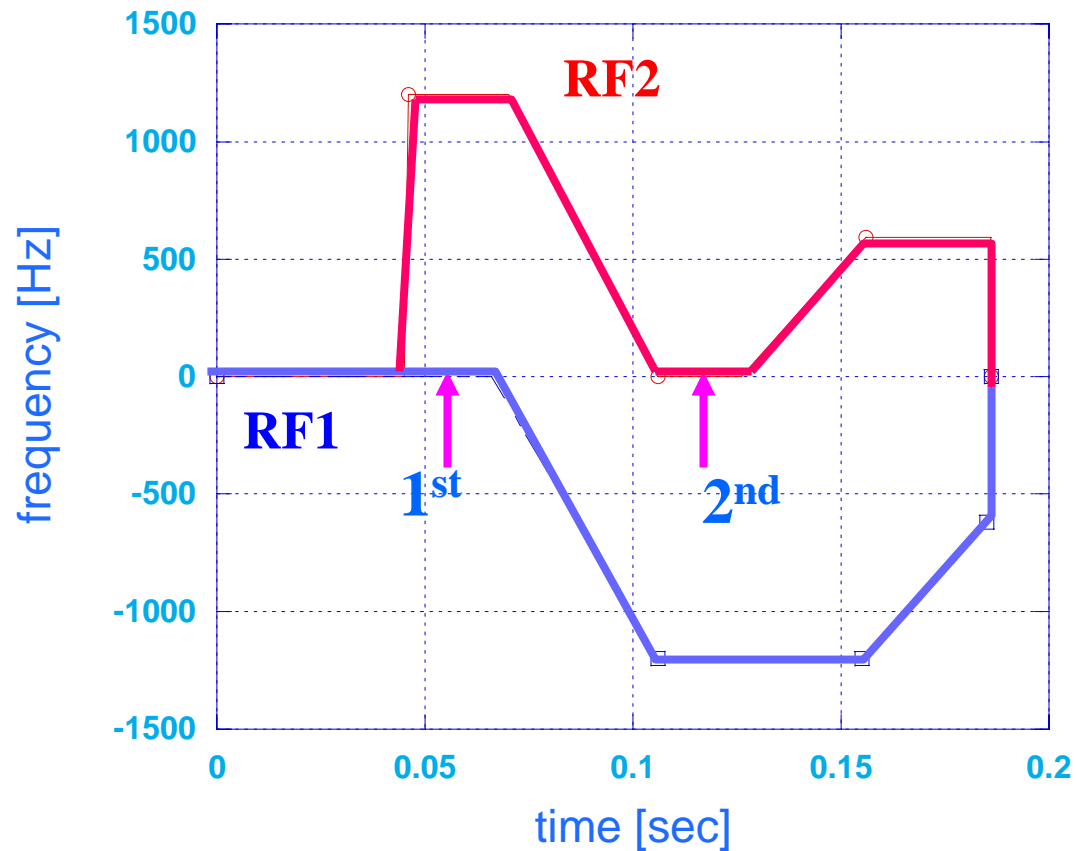
I. Kourbanis, K. Seiya  
MI Collimation Review  
06/30/06

# Slip stacking procedure

(MI has 18 53MHz RF cavities)



# Frequency curves



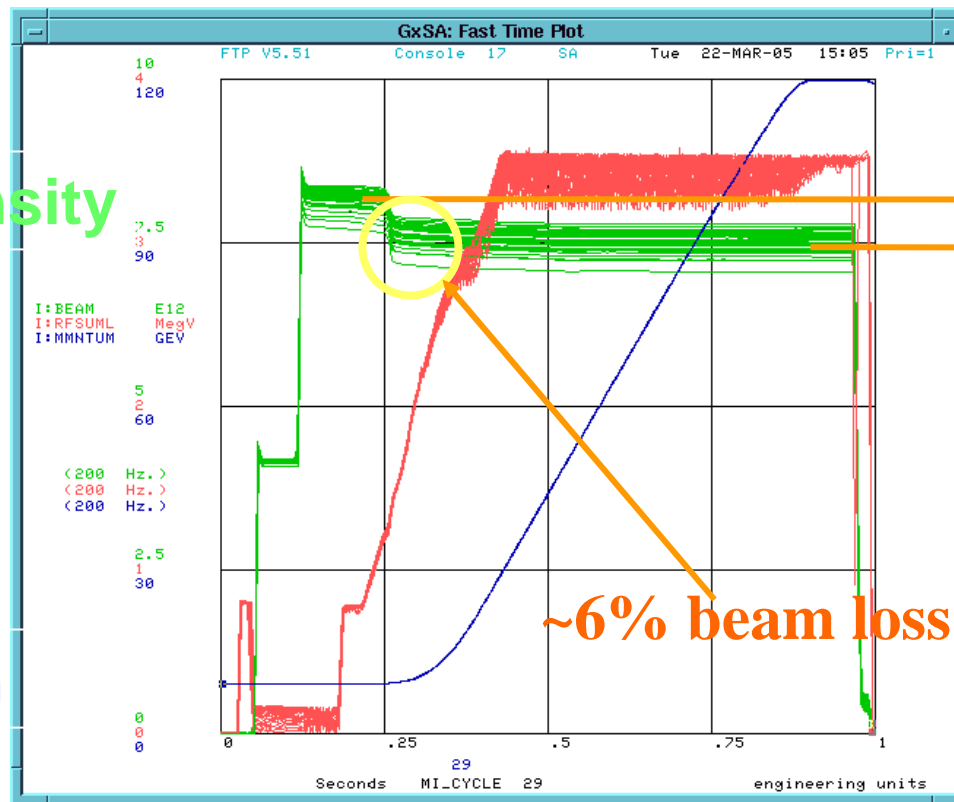
Total slipping time < 3 Booster cycles

# Status in March 2005

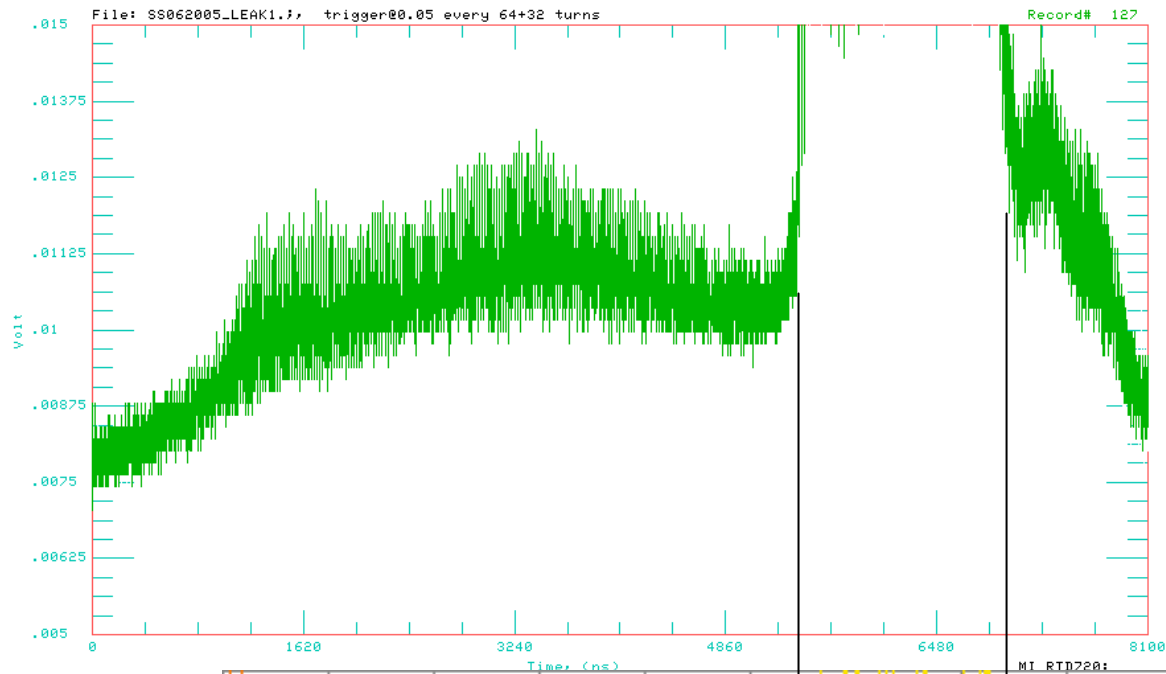
- Intensity on target.:  $7.0\text{E}12$

Beam intensity

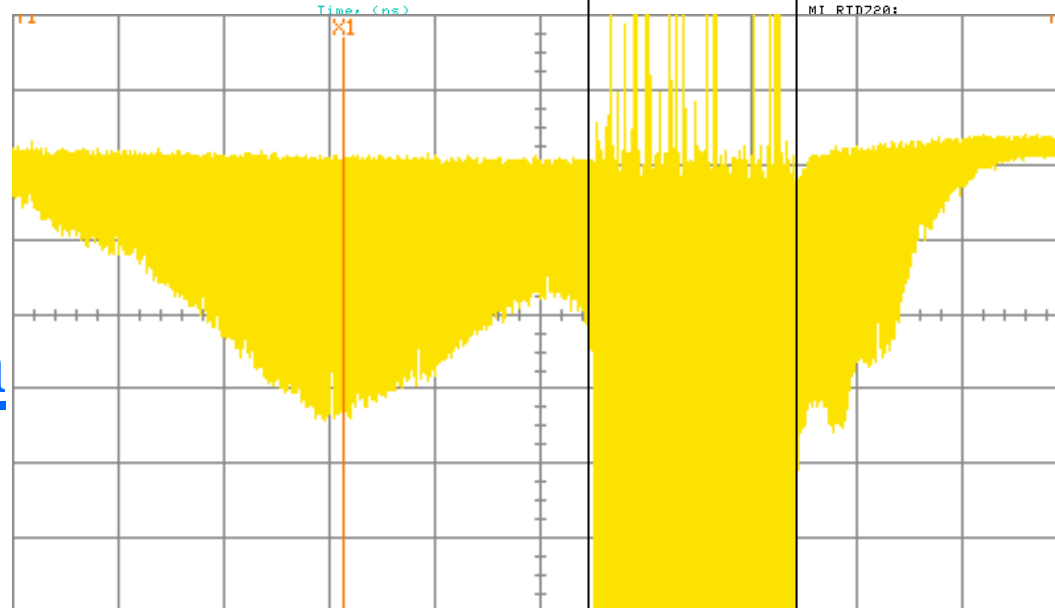
Momentum



# Leaks on WCM signals



@ recapture

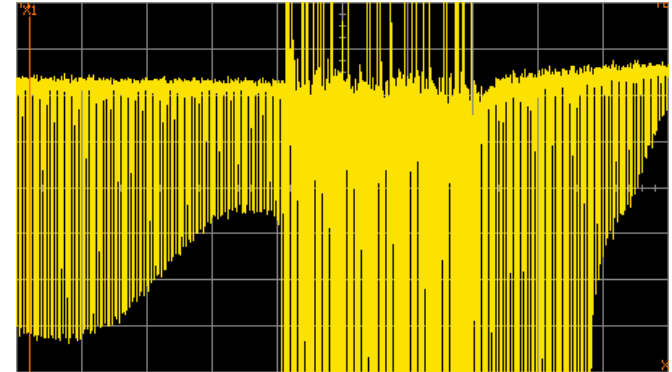
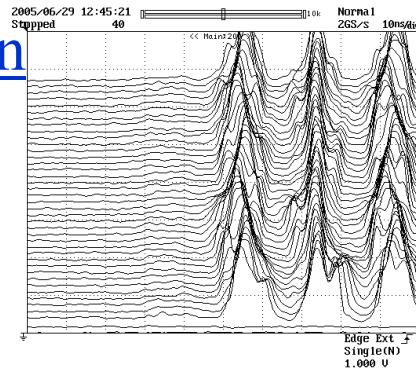


@ extraction

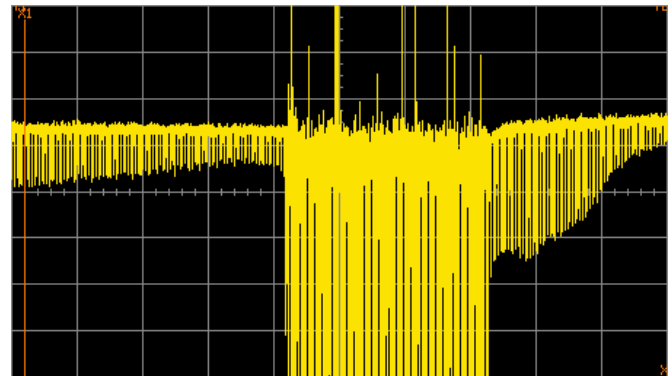
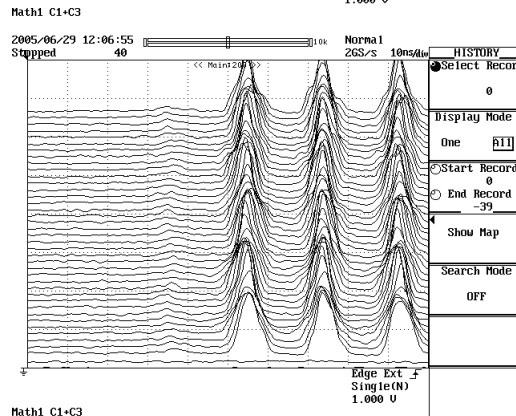
# Mt. range plots @ Injection & WCM signals @ extraction

Intensity @injection

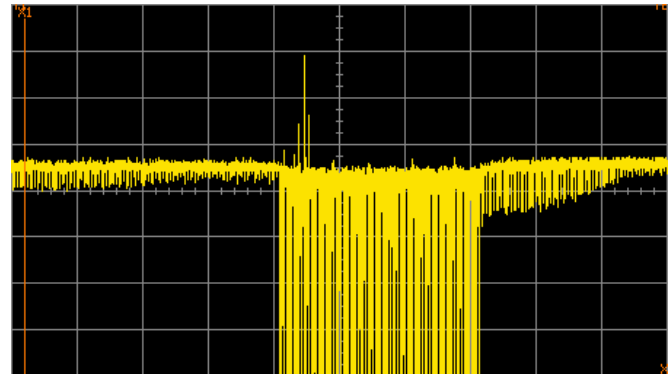
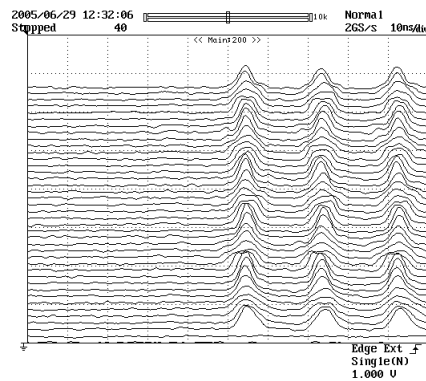
4.0E12



2.5E12



0.8E12



# Improvements in Booster and MI

Booster: Emittance 0.27eV-sec → 0.13 eV-sec

Q-pole damper: Mode 0

D-pole damper: Mode 0,1,2,52

Tuned bunch rotation

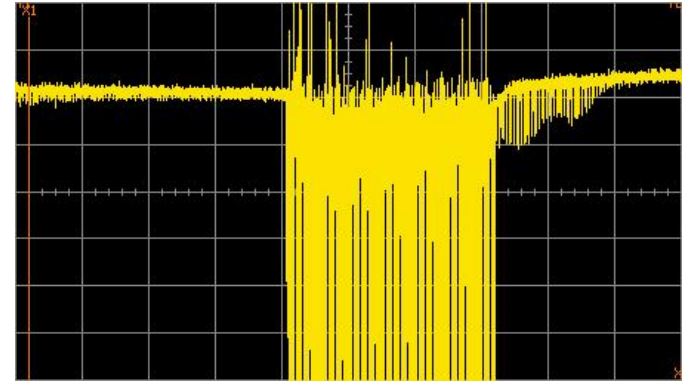
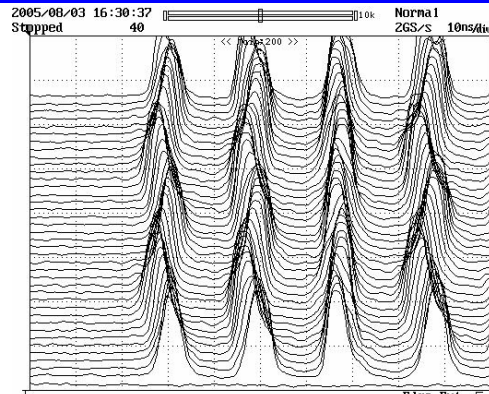
MI: Optimized RF parameters

Frequency separation: 1200Hz → 1400Hz

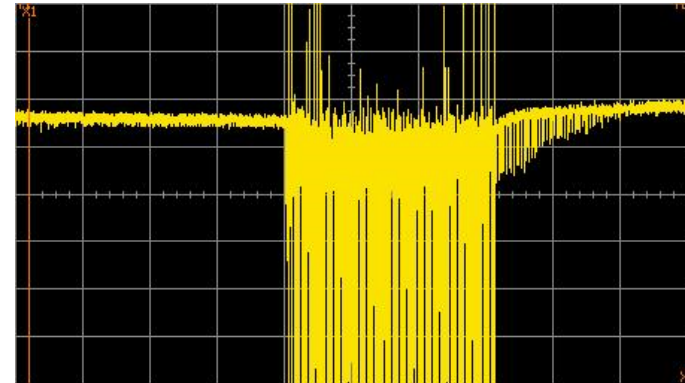
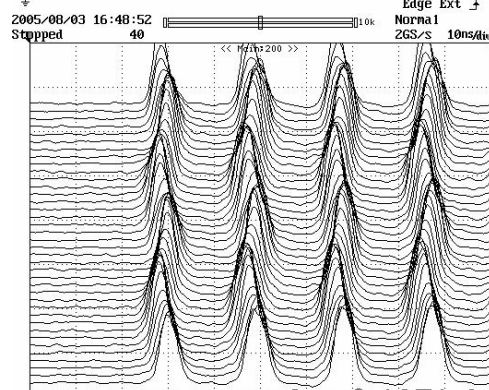
RF voltage for slipping: 90 kV → 110 kV

# Mt. range plots @ Injection & WCM signals at extraction

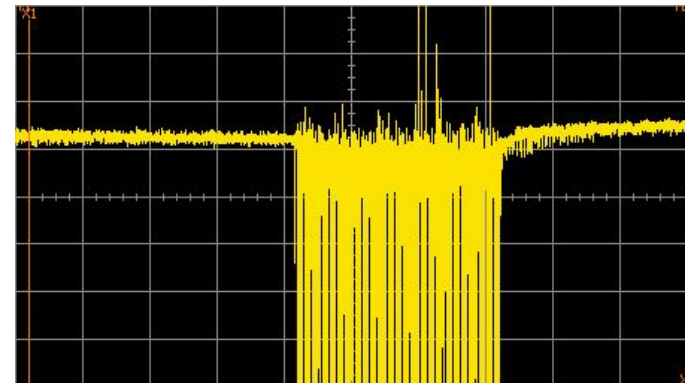
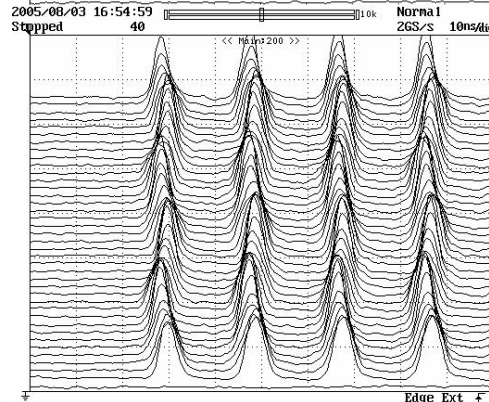
4.0E12



2.5E12



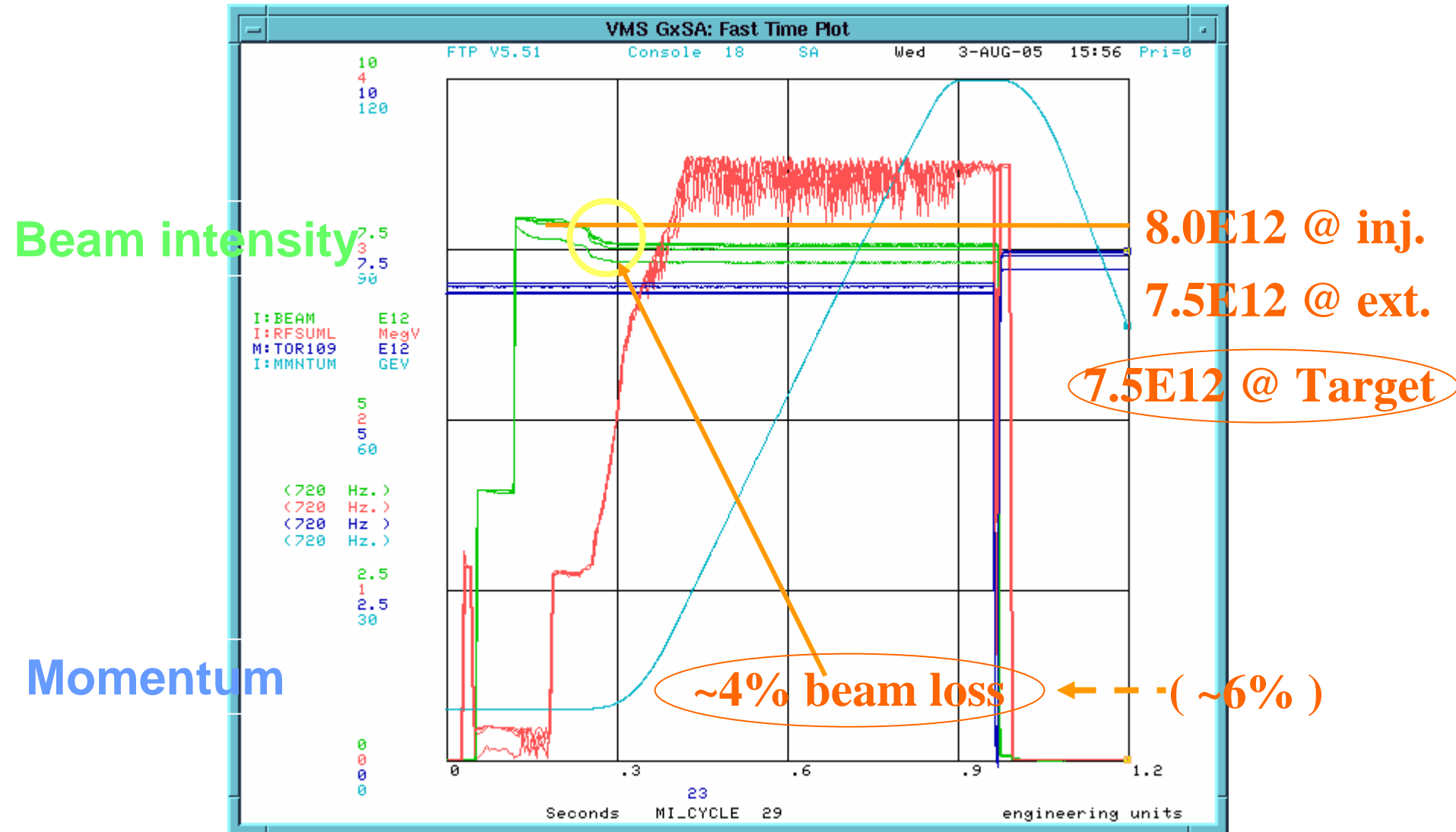
0.8E12





# After beam studies

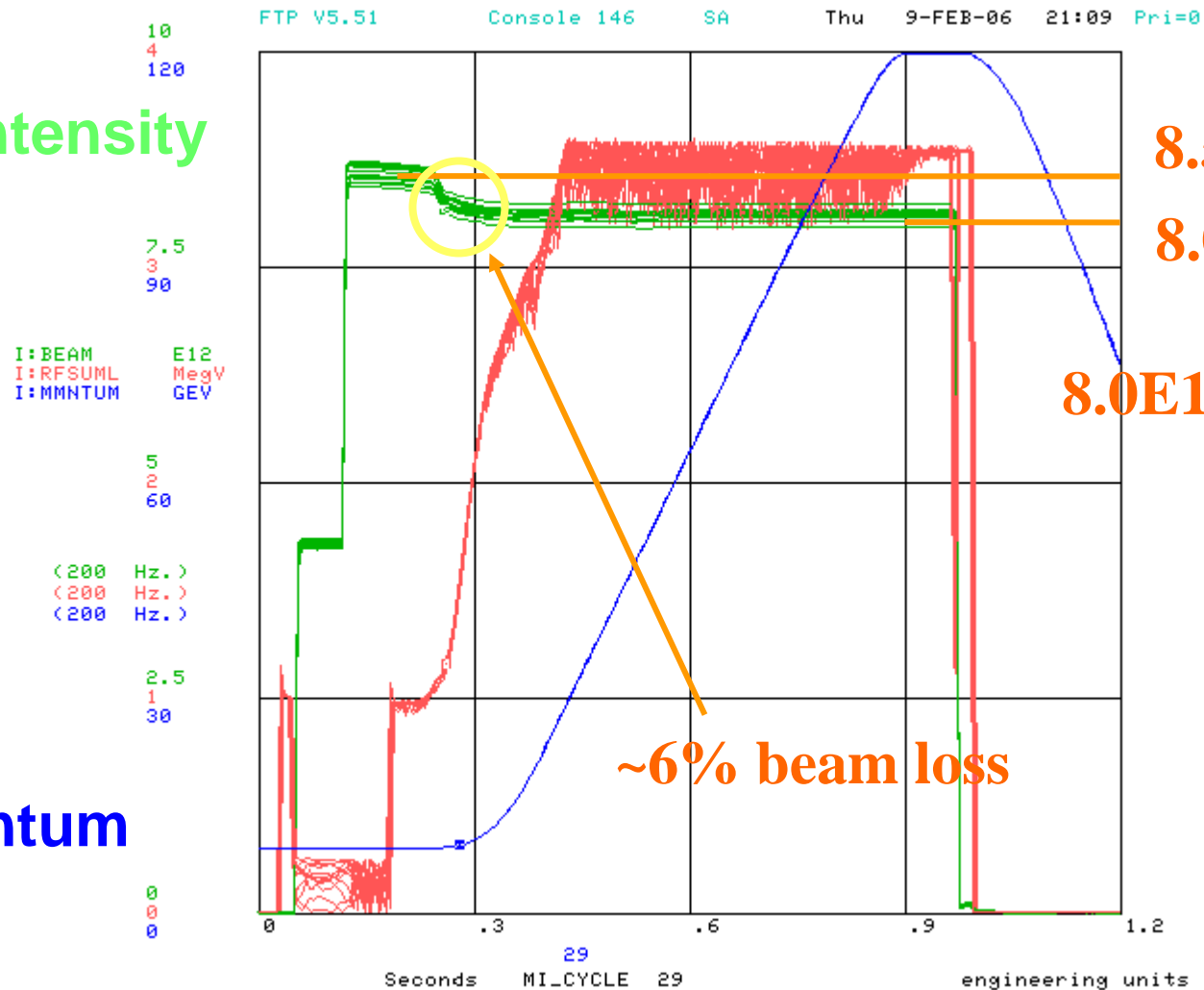
- Intensity on target.:  $7.5\text{E}12$



# Status in February 2006

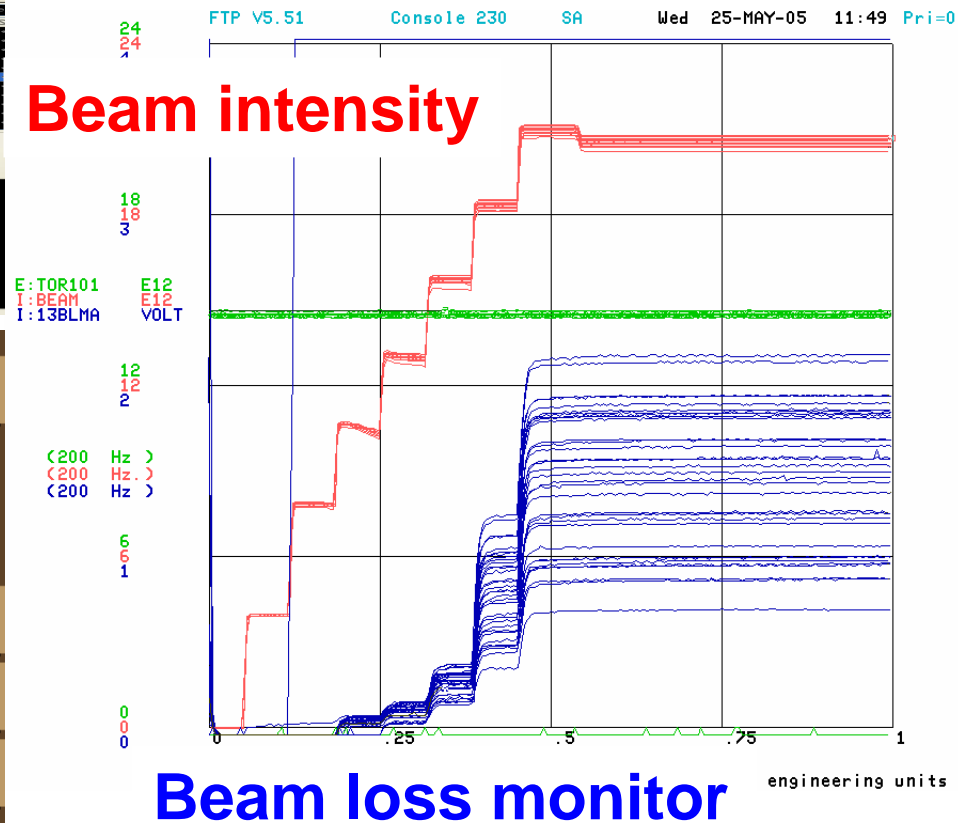
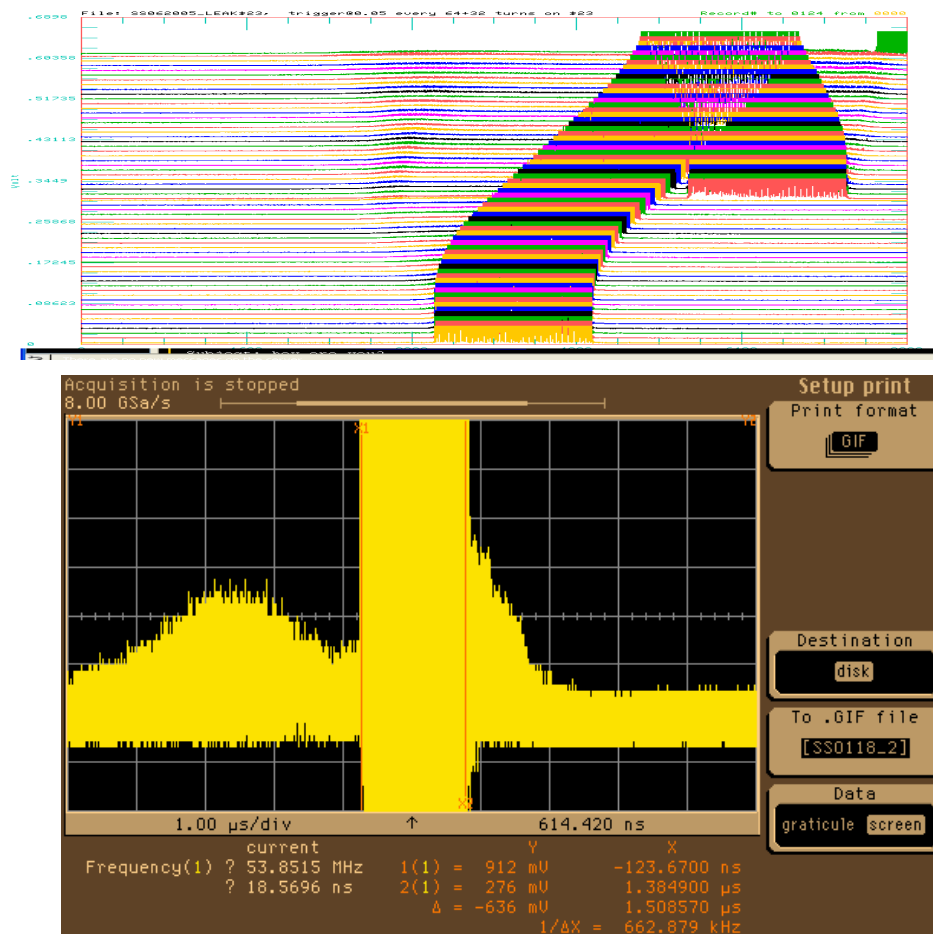
Beam intensity

Momentum

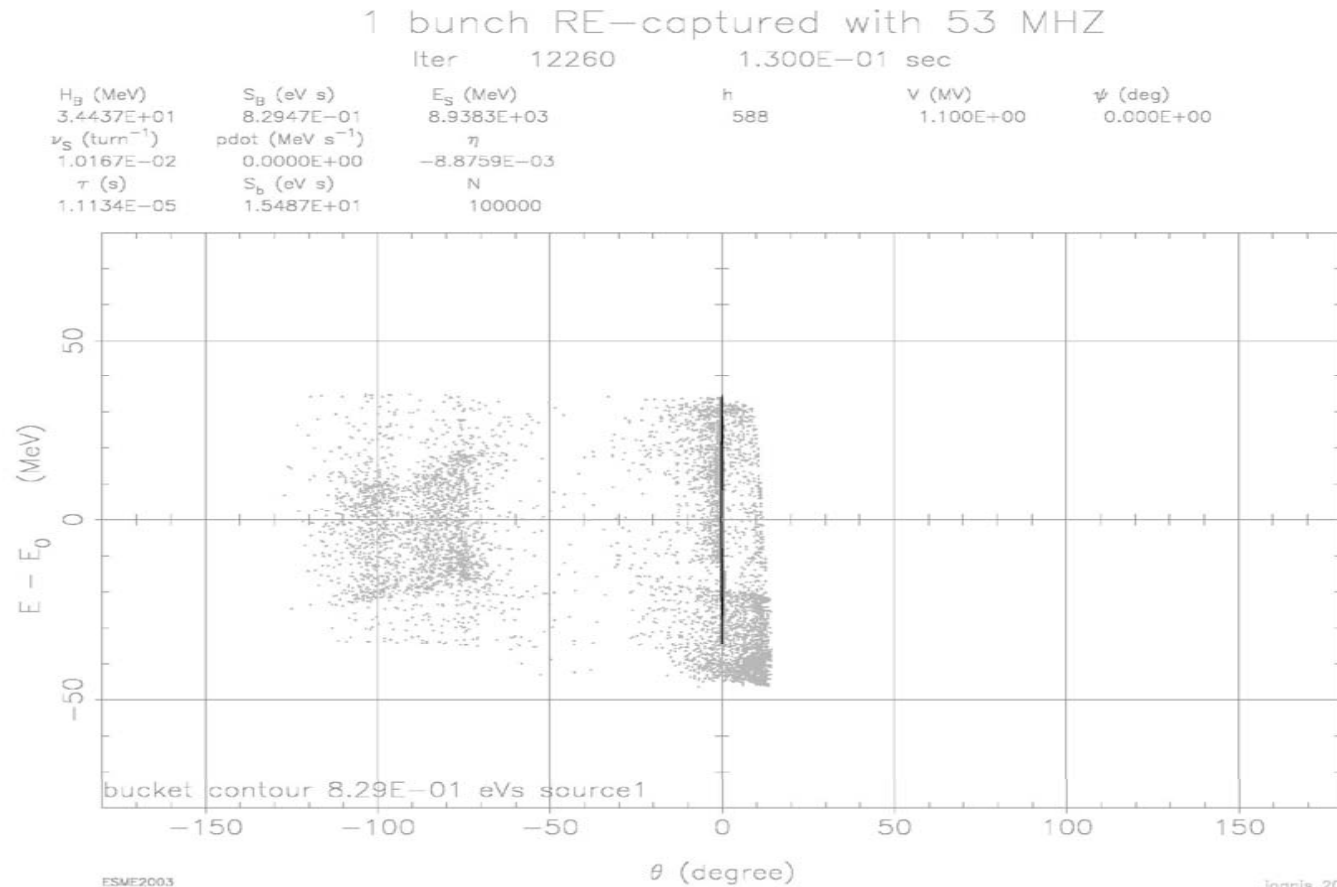


# Beam loss on Injection kicker on current operation

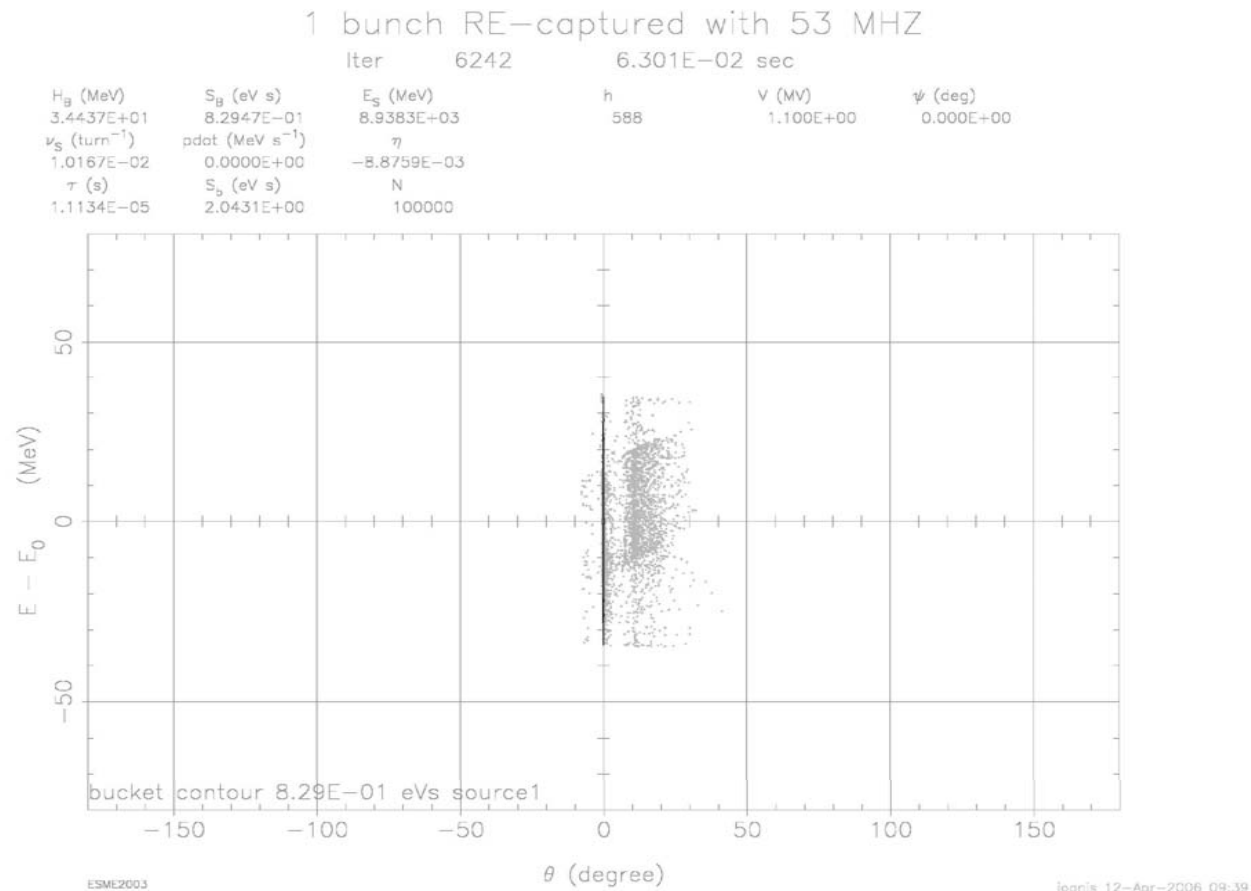
(mixed mode Slip stacking + Numi 5 batches)



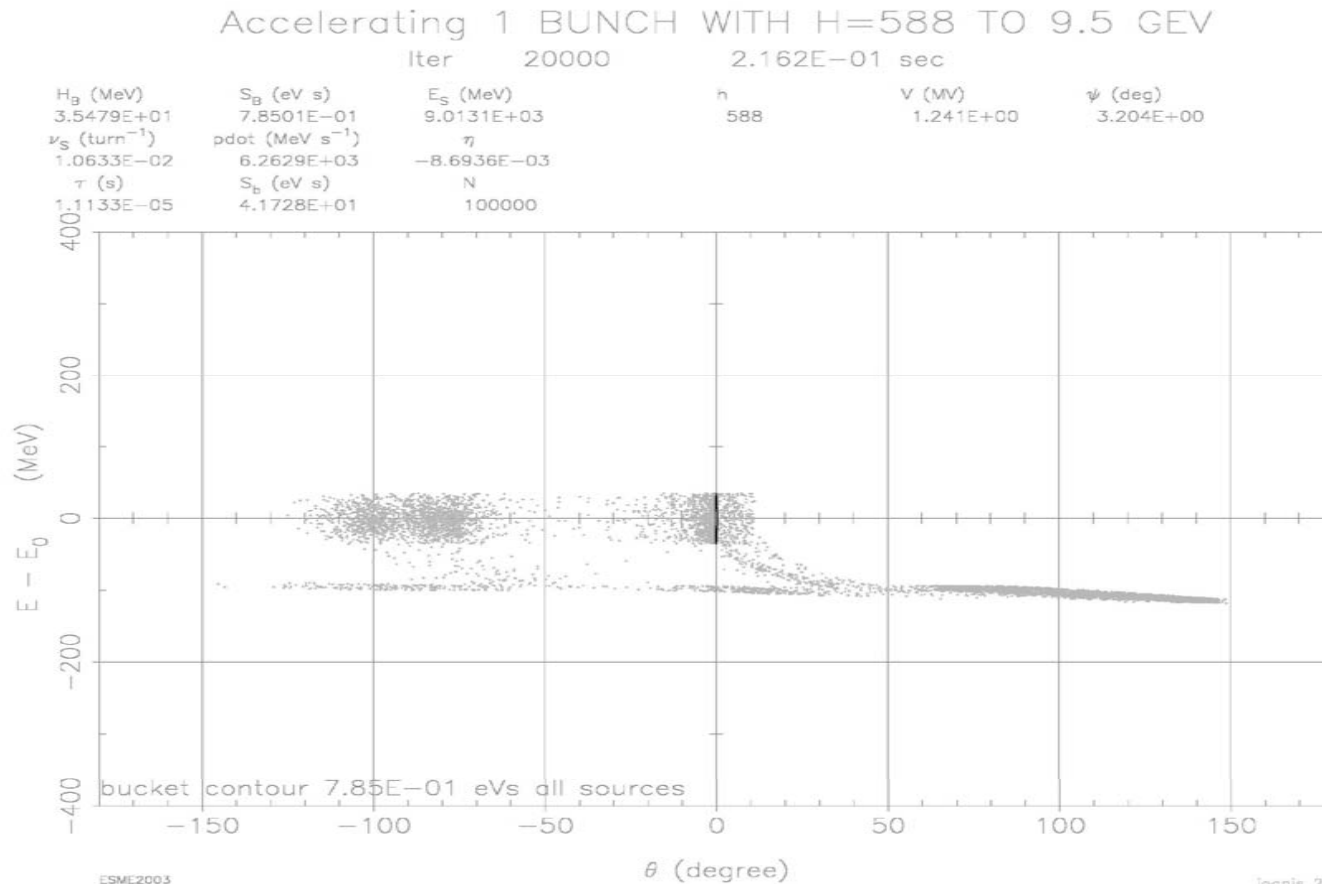
# ESME Simulations of Regular Slip Stacking. First batch (bunch) of 0.18 eV-sec at the time of Recapture.



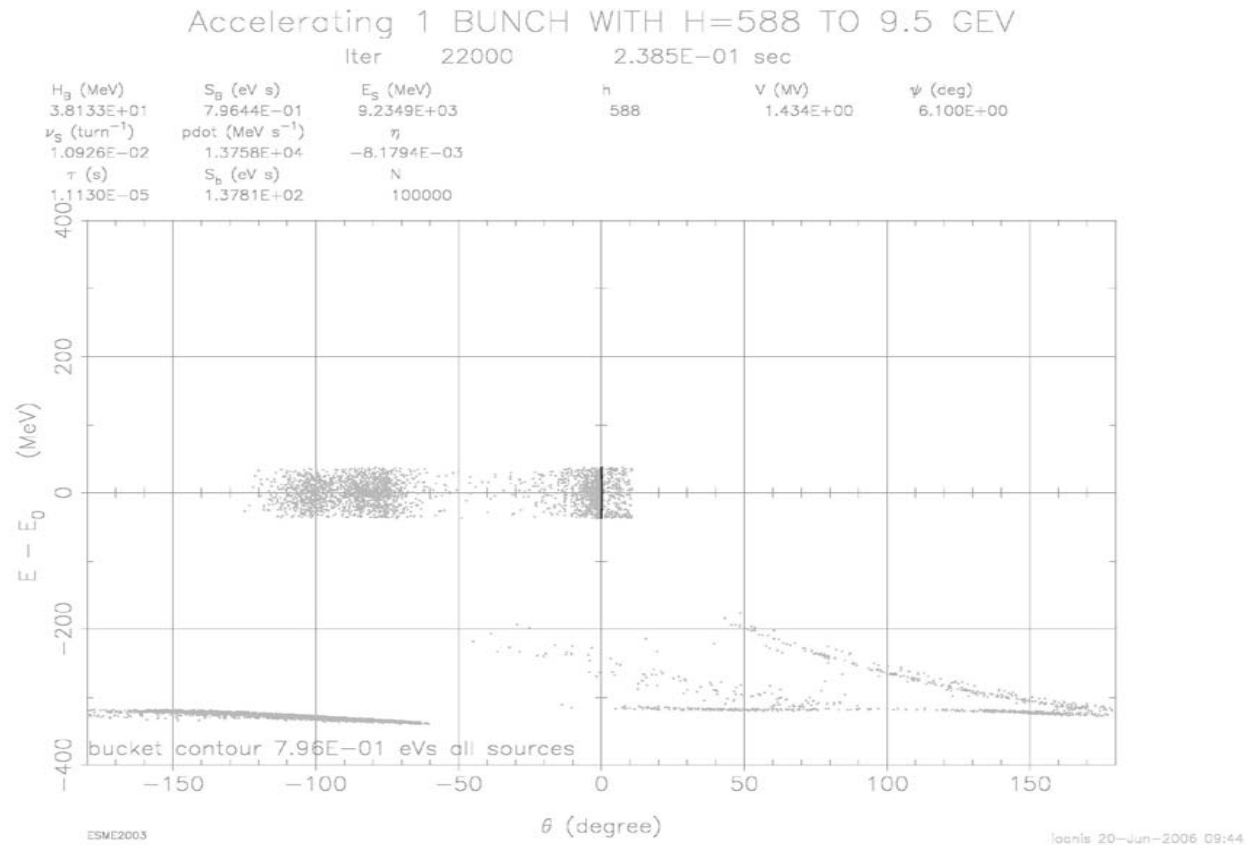
# ESME Simulation of the Regular Slip Stacking. Second batch (bunch) of 0.18 eV-sec at the time of recapture.



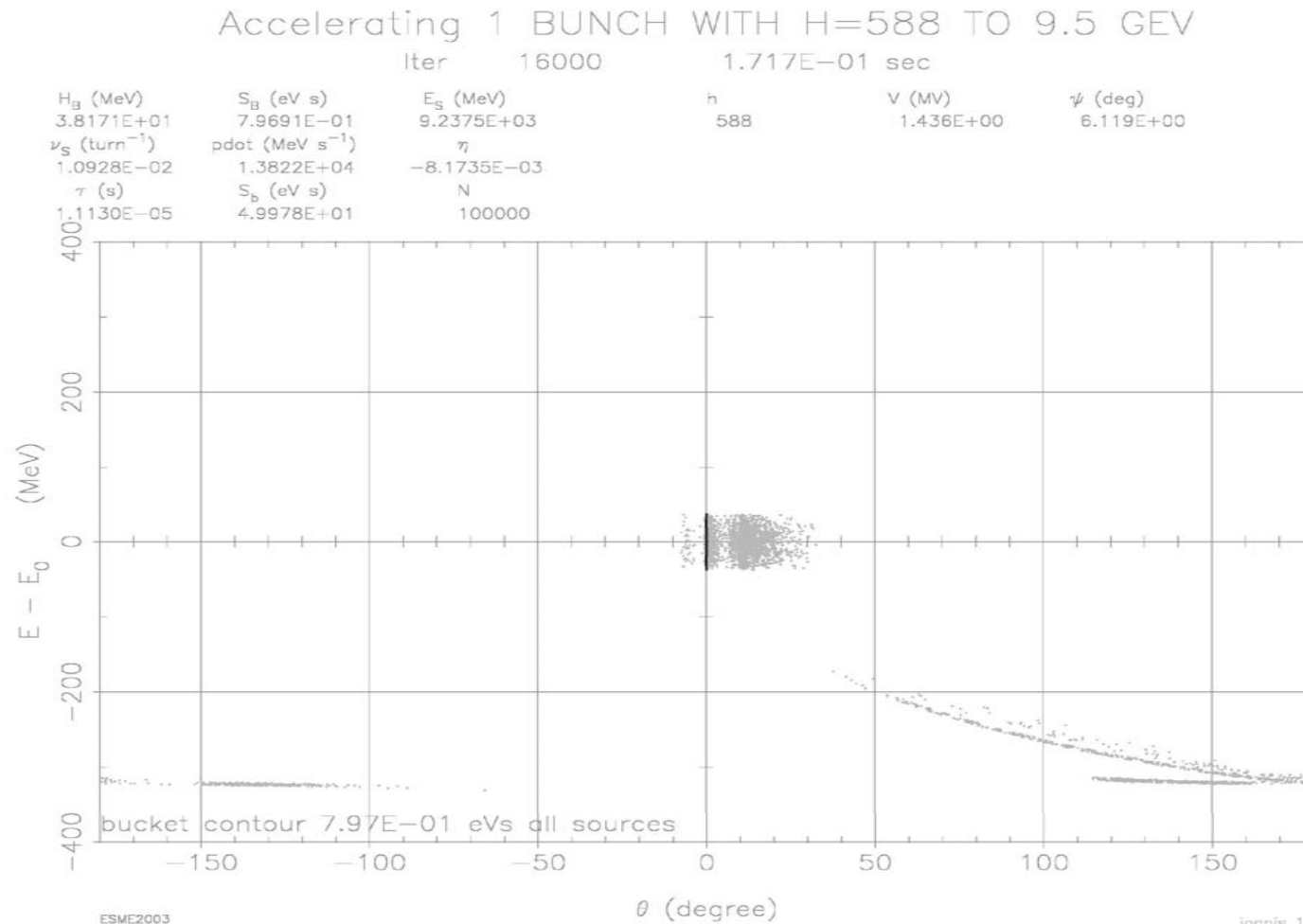
# ESME Simulations of Regular Slip Stacking. Acceleration of the first Batch (bunch)



# ESME Simulations of Regular Slip Stacking. Acceleration of first batch (bunch).



# ESME Simulations of Regular Slip Stacking. Acceleration of the Second Batch (Bunch).

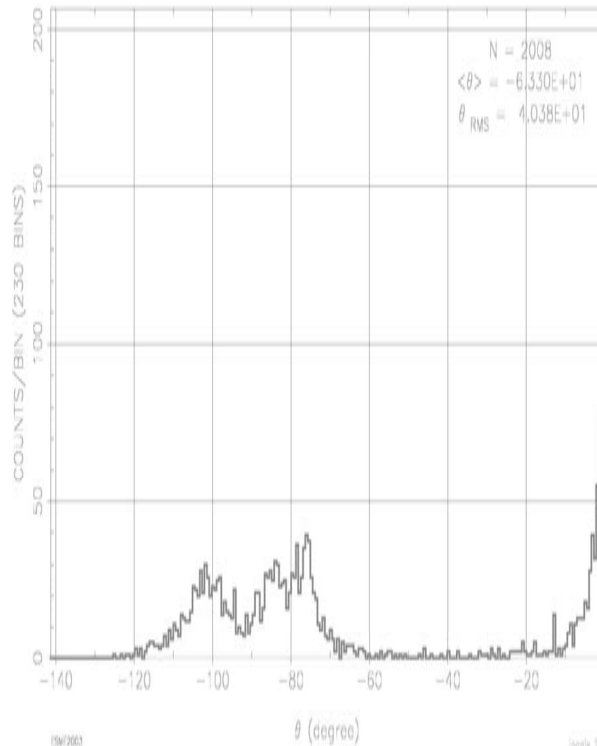




# ESME Simulations of Regular Slip Stacking. Satellite bunch distribution at 120 GeV.

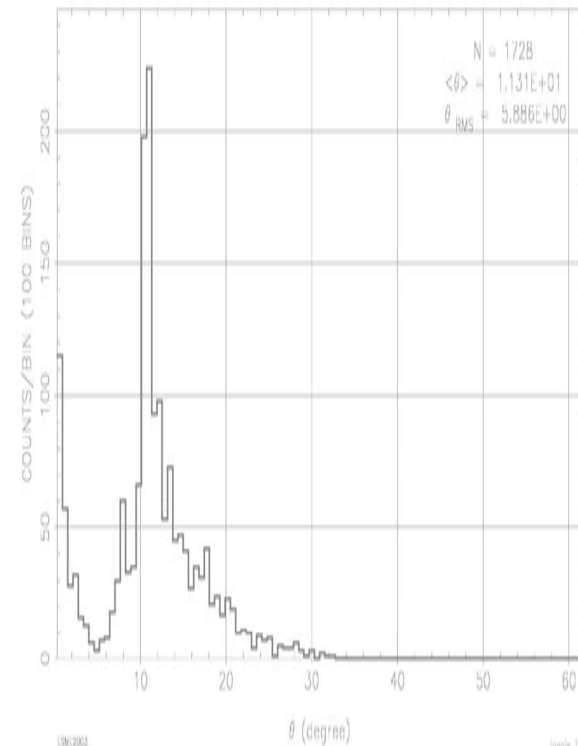
Stay at 120 GeV Early

Iter 88025  
9.699E-01 SEC

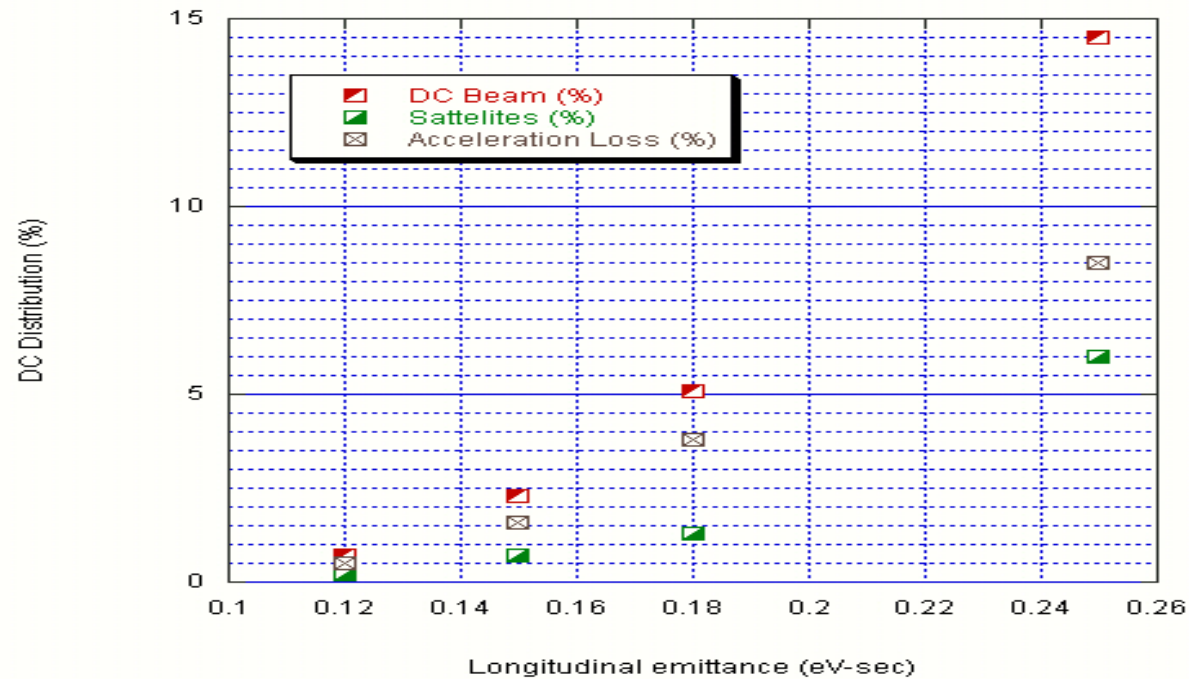


Stay at 120 GeV late

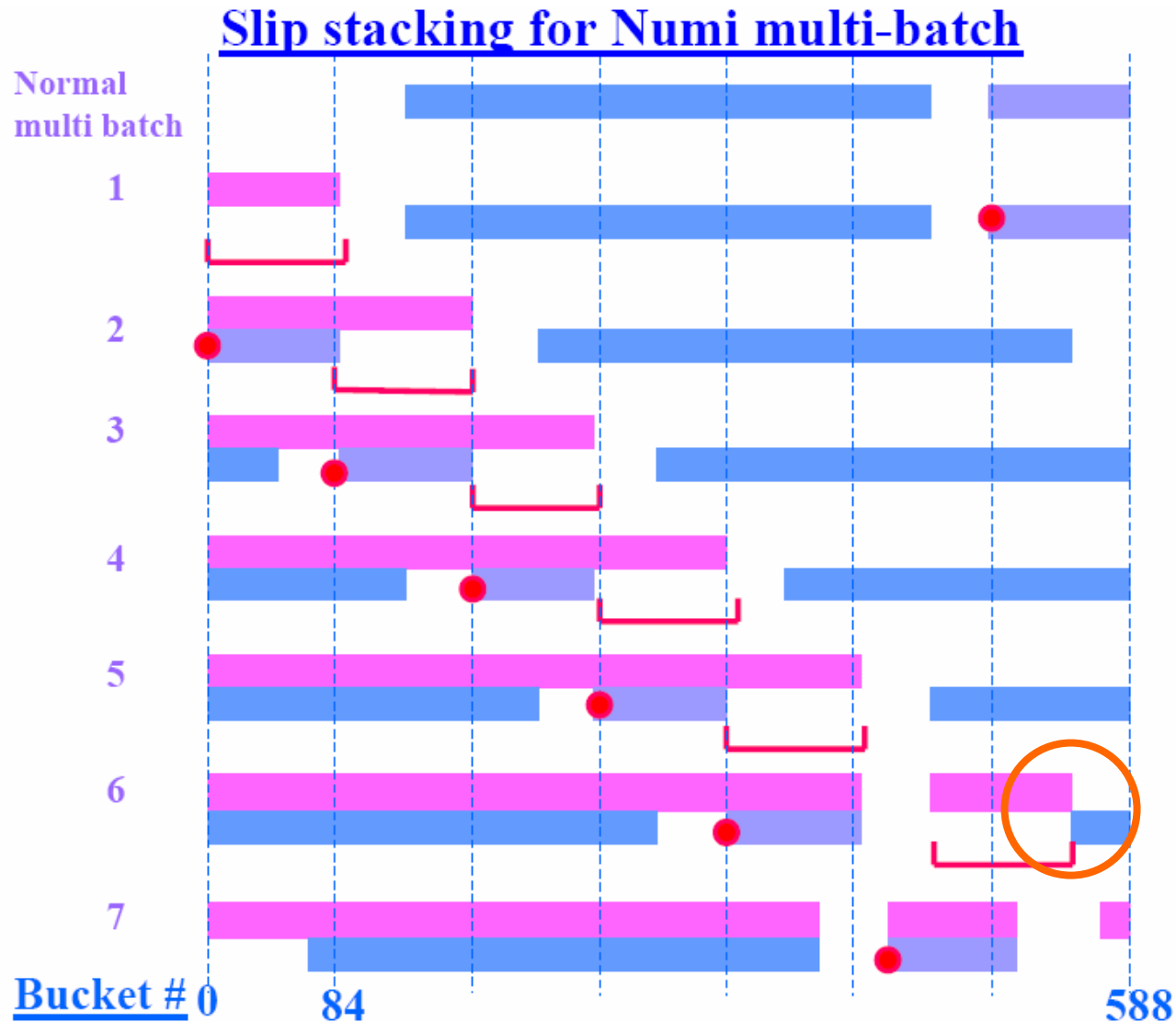
Iter 82008  
9.029E-01 SEC



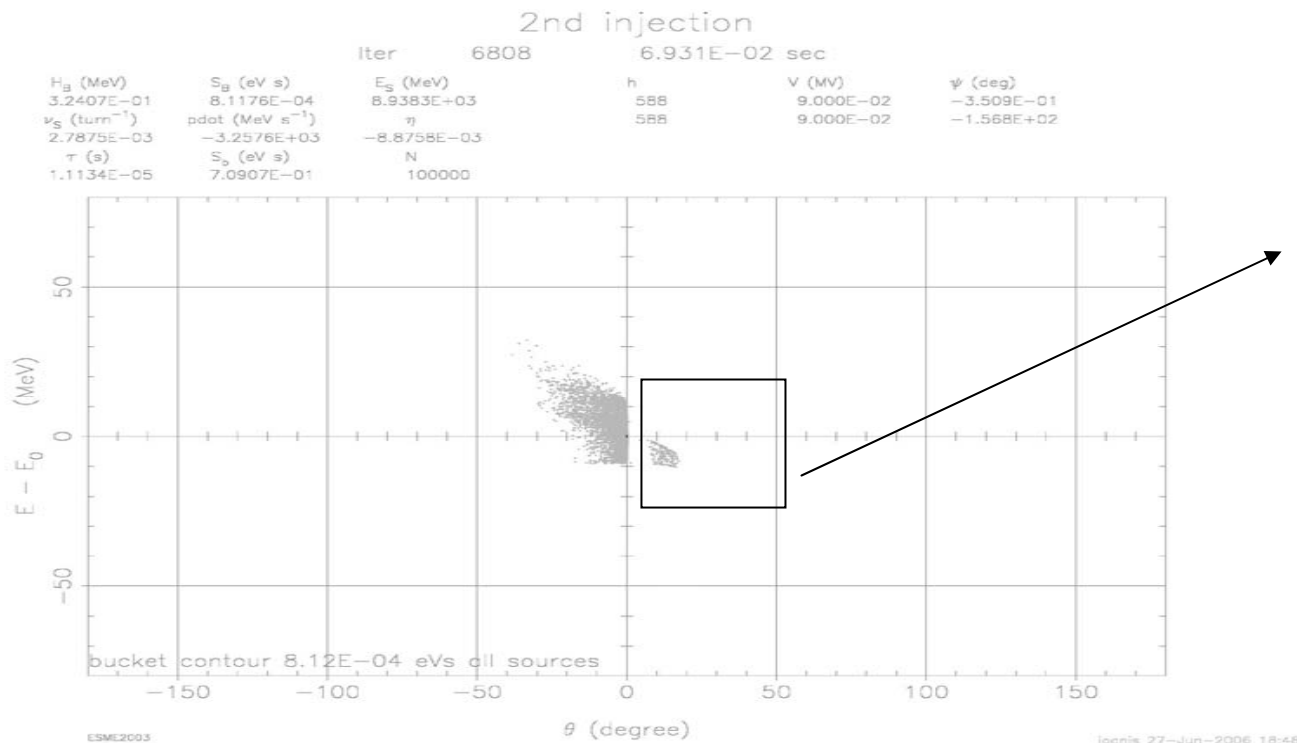
# Loss from Regular Slip Stacking vs LE



# Multi-batch Slip stacking for Numi operation

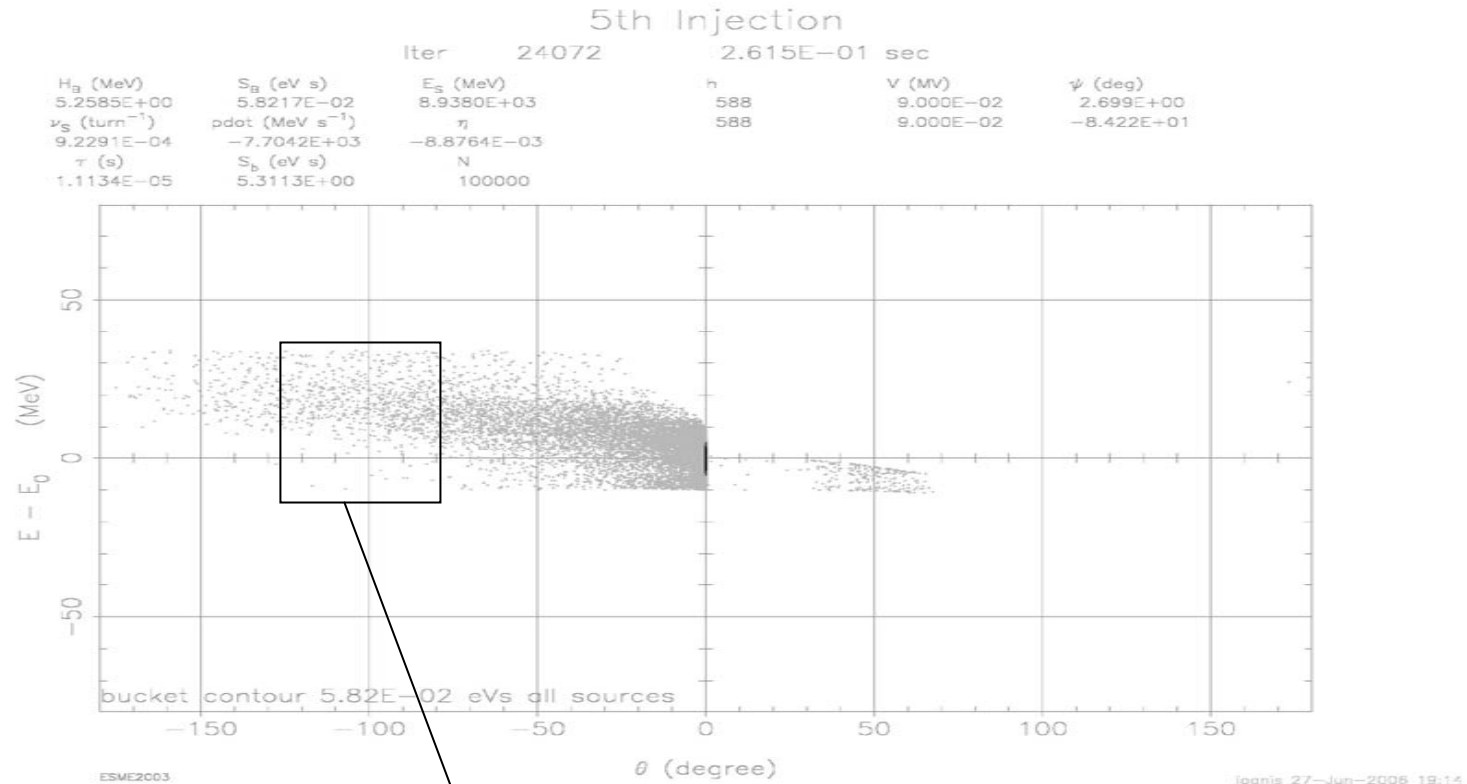


# ESME simulations of Multi-batch slip stacking. First group of Injections. Distribution of particles from the first batch (bunch) at the time of the second injection.



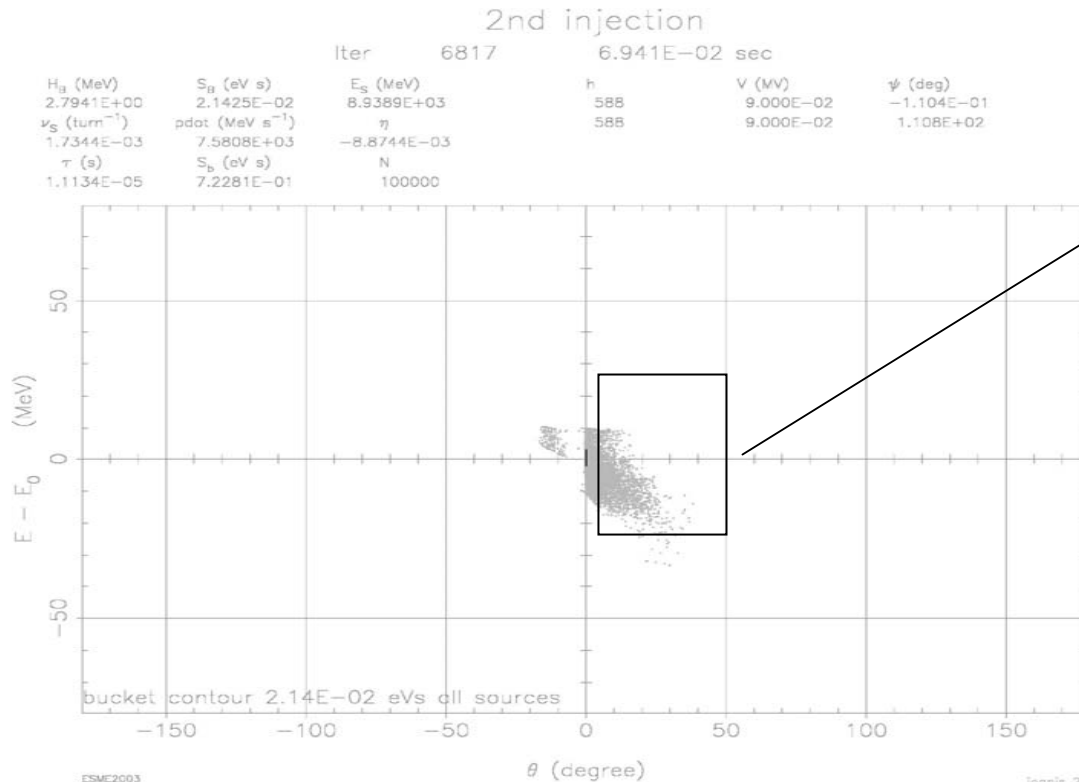
Position of the Second Batch. Very little DC beam is present in the kicker gap.

# ESME simulations of Multi-batch slip stacking. First group of Injections. Distribution of particles from the first batch (bunch) at the time of the fifth injection.



Position of the fifth batch. In this case there is beam in the kicker gap only for the fifth injection.

# ESME Simulations of the multi-batch slip stacking. Second group of injections. Distributions of particles from the first batch (bunch) at the time of the second injection.

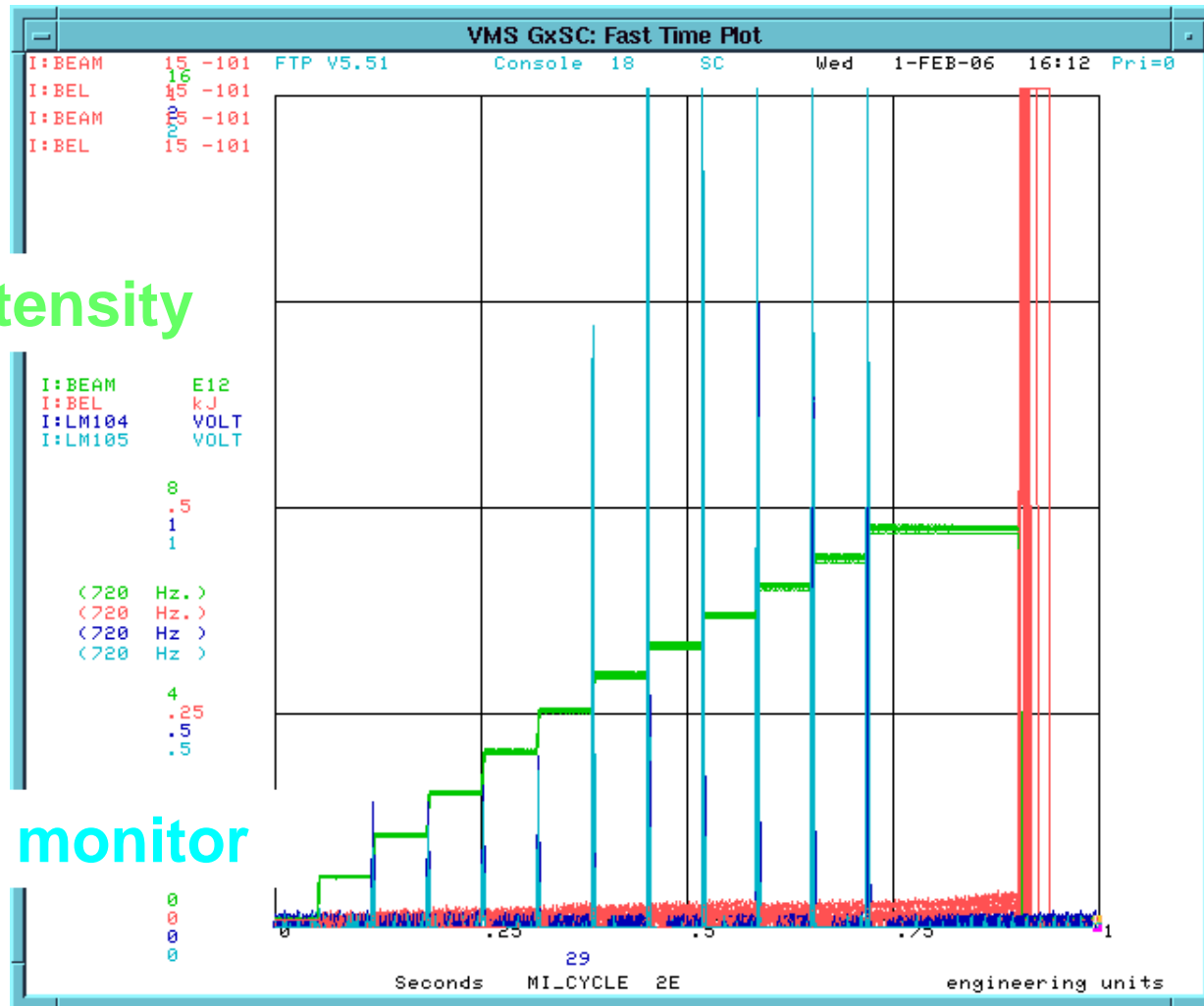


# Multi-batch Slip stacking (beam study)

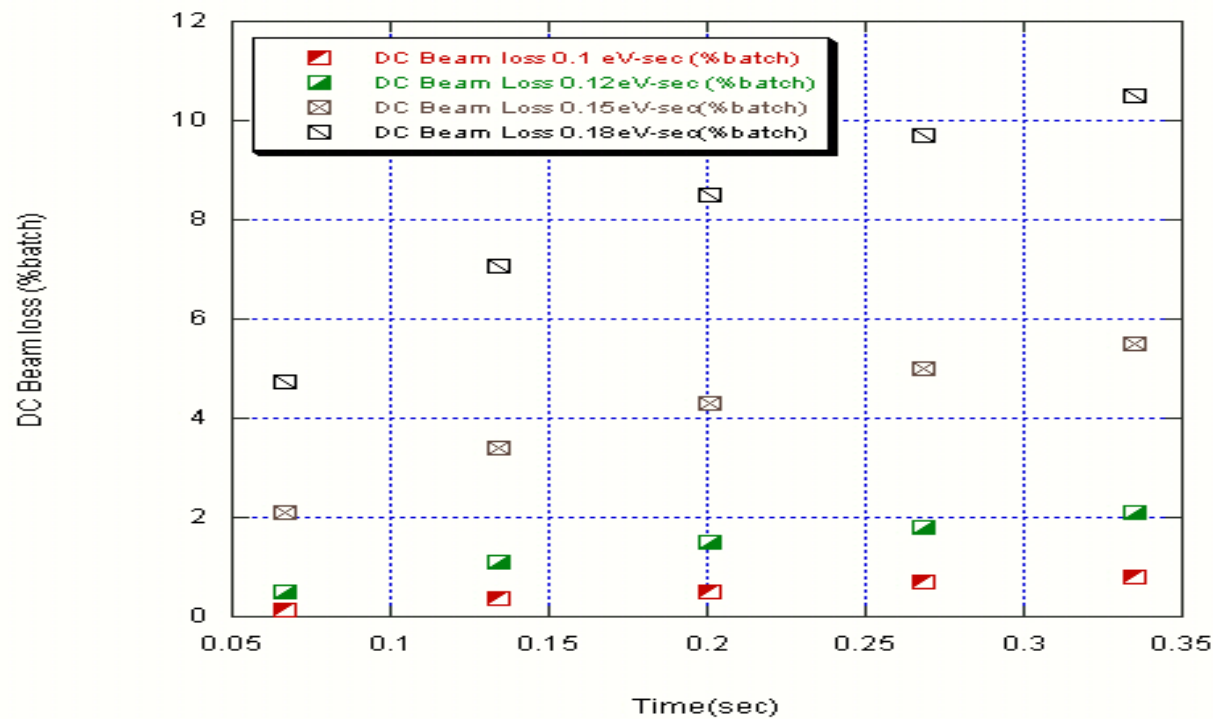
## Beam loss on Injection kicker

Beam intensity

Beam loss monitor

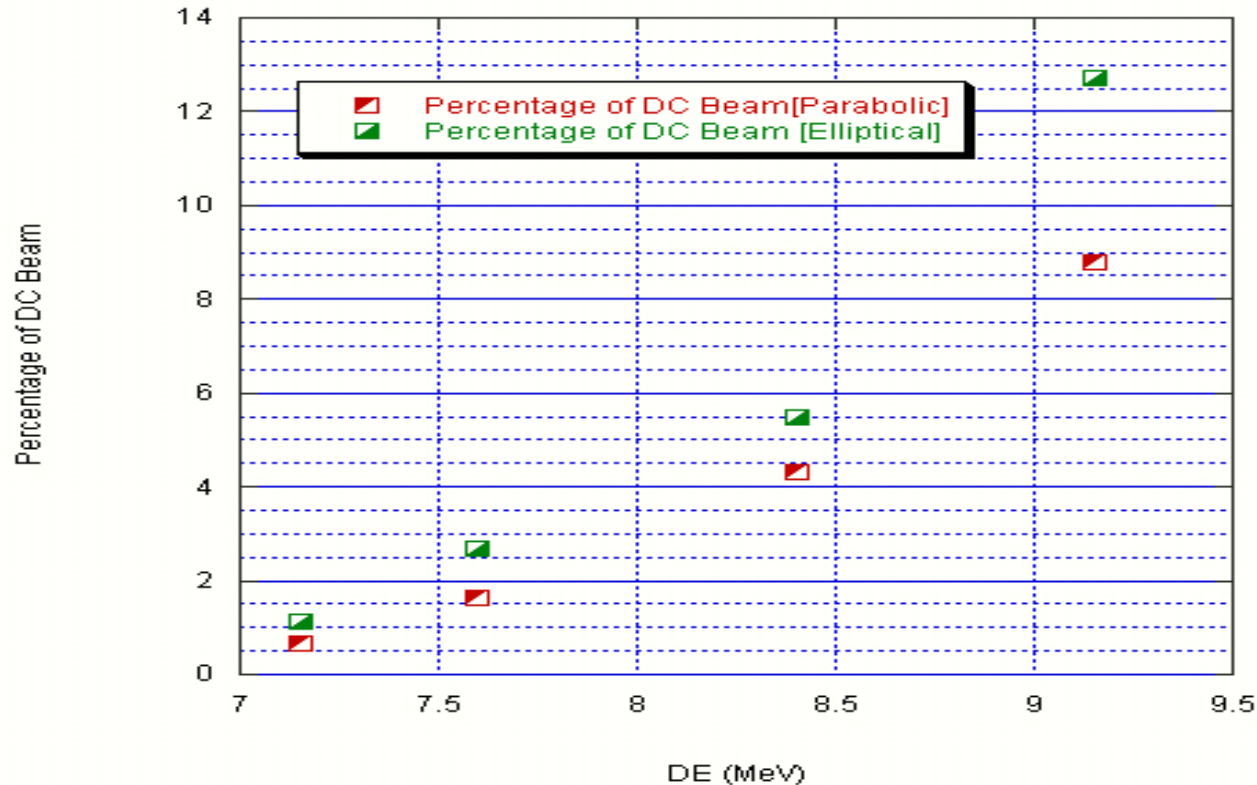


# DC beam as a function of time from Injection for Different long. Emittances.

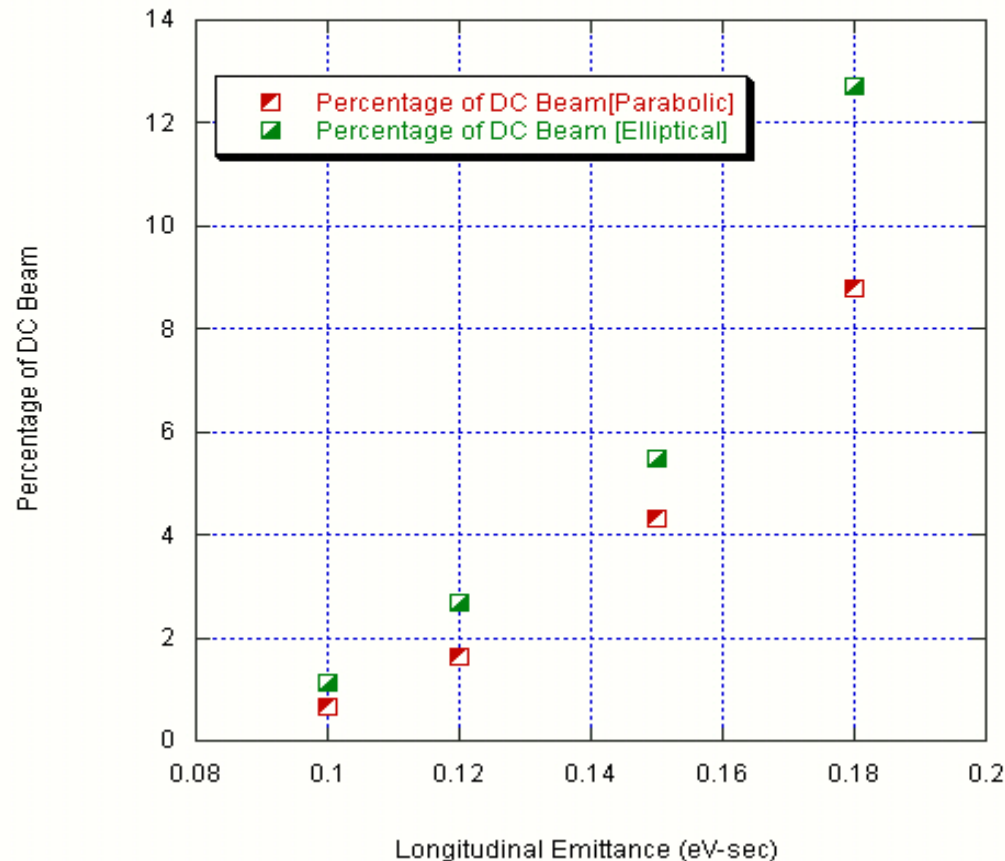




# Total DC Beam generated during multi-batch slip stacking as a function of $D_p$ (Half momentum height)



# Total DC Beam generated during multi-batch slip stacking vs. Long. Emittance



# Conclusions

- ❑ During Slip Stacking we generate uncaptured beam (DC beam) a large fraction of which will be lost during acceleration.
- ❑ The fraction of DC beam depends greatly on the momentum spread of the injected beam.
- ❑ We cannot operate with multi-batch slip stacking without getting rid of the dc beam losses in a controlled way.